

Japan Micropatterning Committee Meeting Summary and Minutes

SEMI Japan Standards Winter 2012 Meetings
Tuesday, December 11, 2012 15:30-17:30
SEMI Japan, Tokyo, Japan

Next Committee Meeting

SEMI Japan Standards Spring 2013 Meetings
Tuesday, April 9, 2013, 15:30-17:30
SEMI Japan, Tokyo, Japan

Table 1 Meeting Attendees

Co-Chair: Iwao Higashikawa (Toshiba)

SEMI Staff: Naoko Tejima (SEMI Japan)

<i>Company</i>	<i>Last</i>	<i>First</i>	<i>Company</i>	<i>Last</i>	<i>First</i>
Toshiba	Higashikawa	Iwao	Dai Nippon Printing	Suzuki	Toshio
Toppan Printing	Otaki	Masao	SEMI Japan	Tejima	Naoko

** alphabetical order by last name*

Table 2 Leadership Changes

None

Table 3 Ballot Results

Passed ballots and line items will be submitted to the ISC Audit & Review Subcommittee for procedural review.

Failed ballots and line items were returned to the originating task forces for re-work and re-balloting.

<i>Document #</i>	<i>Document Title</i>	<i>Committee Action</i>
5483	Reapproval of SEMI P47-0307, Test Method for Evaluation of Line-edge roughness and Line-width Roughness	Passed as balloted

Table 4 Authorized Ballots

<i>#</i>	<i>When</i>	<i>SC/TF/WG</i>	<i>Details</i>
5535	C1-13	5-year-review Task Force	Reapproval of SEMI P35-1106, Terminology for Microlithography Metrology
5536	C1-13	5-year-review Task Force	Reapproval of SEMI P36-1108, Guide for Magnification Reference for Critical Dimension Measurement for Scanning Electron Microscopes (CD-SEMS) (with Editorial Changes)

Table 5 Authorized Activities

#	Type	SC/TF/WG	Details
5535	SNARF	5-year-review Task Force	Reapproval of SEMI P35-1106, Terminology for Microlithography Metrology
5536	SNARF	5-year-review Task Force	Reapproval of SEMI P36-1108, Guide for Magnification Reference for Critical Dimension Measurement for Scanning Electron Microscopes (CD-SEMS) (with Editorial Changes)
5537	SNARF	5-year-review Task Force	Line Item Revision to SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection Systems

Note: SNARFs and TFOFs are available for review on the SEMI Web site at:
<http://downloads.semi.org/web/wstdsbal.nsf/TFOFSNARF>

Table 6 New Action Items

Item #	Assigned to	Details
MP120828-1	Mask Data Format for Mask Tools Task Force	To prepare the information (blue) ballot of Doc. 5229, Revision to SEMI P44, as soon as possible.
MP120828-2	5 Year Review Task Force	To draft the document of Doc. 5484, Revision to SEMI P22-0307, by January 31.
MP121211-1	5 Year Review Task Force	To draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200, by the next committee meeting (April 9).
MP121211-2	SEMI Staff	To send the TF members the Word file of SEMI P23-0200 to draft the Line Item Revision documents
MP121211-3	SEMI Staff	To prepare SNARFs and Reapproval ballots of SEMI P35 and P36 for Cycle 1, 2013

1 Welcome, Reminders and Introductions

Iwao Higashikawa, committee co-chair, called the meeting to order at 15:30. Self-introductions were made followed by the agenda review.

2 Required Meeting Elements

The meeting reminders on program membership requirement, antitrust issues, intellectual property issues and international effective meeting guidelines, were reviewed by SEMI staff, Naoko Tejima.

3 Review of Previous Meeting Minutes

The committee reviewed the minutes of the previous meeting held on August 28, 2012.

- Motion:** To approve the minutes of the previous meeting as written.
By / 2nd: Masako Otaki (Toppan Printing) / Toshio Suzuki (Dai Nippon Printing)
Discussion: None
Vote: 2 in favor and 0 opposed. **Motion passed.**
Attachment: 01_JA_Micropatterning_Previous_Mtg_Minutes_121211

4 SEMI Staff Report

Naoko Tejima gave the SEMI staff report. This report included SEMI Global 2012-2013 Calendar of Events, SEMICON Japan 2012, 2012 Standards Awards, 2013 Critical Dates for SEMI Standards Ballots, Regulation SC Report, A&R SC Report, SEMI Standards Publication, New Standards Ballot and Membership Systems, New Ballot Formatting Templates, Style Manual and Compilation of Terms and Contact Information.

Attachment: 02_SEMI_Staff_Report_121211

5 Liaison Reports

5.1 North America Microlithography Committee Report

No report was provided.

6 Ballot Review

6.1 Doc.5483 "Reapproval of SEMI P47-0307, Test Method for Evaluation of Line-edge roughness and Line-width Roughness" passed committee review as balloted and will be forwarded to the ISC A&R SC for procedural review.

Action Item: SEMI staff to forward adjudication result of Doc.5483 to the ISC A&R Subcommittee for procedural review.

Attachment: 03_Ballot_Report_for_5483_121211

7 Task Force Reports

7.1 Mask Data Format for Mask Tools Task Force

Toshio Suzuki reported for the Mask data Format for Mask Tools Task Force. Of note:

- Task Force meeting will be held in late January and the information (blue) ballot of *Doc. 5229, Revision to SEMI P44, Specification for Open Artwork System Interchange Standard (OASIS) Specific to Mask Tools*, will be issued after the meeting. The letter (yellow) ballot will be submitted for cycle 3 in 2013.

Action Item: Mask Data Format for Mask Tools Task Force to prepare the information (blue) ballot of Doc. 5229 as soon as possible.

7.2 5 Year Review Task Force

7.2.1 SEMI P23-0200 (Reapproved 1107)

Iwao Higashikawa reported that the following document is due for 5-year-review.

- SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection Systems
- Masao Otaki pointed some parts of SEMI P23 should be corrected or deleted. TF decided to review it and submit the line item ballot for the earliest possible cycle.

Motion: To approve a new SNARF for Line Item Revisions to SEMI P23-1107

By / 2nd: Masako Otaki (Toppan Printing) / Toshio Suzuki (Dai Nippon Printing)

Discussion: None.

Vote: 2 in favor and 0 opposed. **Motion passed.**

Attachment: 04_SNARF_of_SEMI-P23_121211

Action Item: 5 Year Review Task Force to draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection Systems by the next committee meeting (April 9).

Action Item: SEMI Staff to send the TF members the Word file of SEMI P23-0200 to draft the Line Item Revision documents

7.2.2 SEMI P35-1106 & SEMI P36-1108

Iwao Higashikawa reported that the following documents are due for 5-year-review.

- SEMI P35-1106, Terminology for Microlithography Metrology
- SEMI P36-1108, Guide for Magnification Reference for Critical Dimension Measurement Scanning Electron Microscopes (CD-SEMS)
- The Task Force agreed to submit reapproval ballot of the above for Cycle 1, 2013.

Motion: To submit SEMI P35-1106 Reapproval ballot for Cycle 1, 2013.
By / 2nd: Masako Otaki (Toppan Printing) / Toshio Suzuki (Dai Nippon Printing)
Discussion: None.
Vote: 2 in favor and 0 opposed. **Motion passed.**

Motion: To submit SEMI P36-1108 Reapproval ballot with editorial changes for Cycle 1, 2013.
By / 2nd: Masako Otaki (Toppan Printing) / Toshio Suzuki (Dai Nippon Printing)
Discussion: None.
Vote: 2 in favor and 0 opposed. **Motion passed.**

Action Item: SEMI staff to prepare SNARFs and Reapproval ballots of SEMI P35 and P36 for Cycle 1, 2013

7.2.3 SEMI P22-0307

Masao Otaki reported on the progress for the Revision to SEMI P22-0307. Of note:

- Task Force is drafting the document of Doc. 5484, Revision to SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition.
- The Task Force is planning to finish the draft document by the end of January and submit the letter ballot for the earliest possible cycle, 2013.

Action Item: 5 Year Review Task Force to draft the document of Doc. 5484, Revision to SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition by January 31.

8 Old Business

8.1 Previous Meeting Action Items

Naoko Tejima reviewed the previous meeting action items.

Table 7 Previous Meeting Actions Items

Item #	Assigned to	Details
MP120828-1	Mask Data Format for Mask Tools Task Force	To prepare the information (blue) ballot of Doc. 5229 by October 31 as soon as possible. ... Open
MP120828-2	5 Year Review Task Force	To draft the document of Doc. 5484 by December 31 January 31. ... Open
MP120828-3	SEMI Staff	To prepare reapproval ballot of SEMI P47. ... Closed
MP120828-4	SEMI Staff	To send the documents which are due for 5-year-review (SEMI-P23, SEMI-P35, SEMI-P36) to Iwao Higashikawa, Masao Otaki and Toshio Suzuki so that they can judge whether they should be revised or not. ... Closed
MP120828-5	Iwao Higashikawa, Masao Otaki and Toshio Suzuki	To review SEMI P23-0200, SEMI P35-1106, SEMI P36-1108 and discuss that they should be revised or not. ... Closed

9 New Business

None



10 Action Item Review

10.1 New Action Items

Naoko Tejima reviewed the new action items. These can be found in the New Action Items table at the beginning of these minutes.

11 Next Meeting and Adjournment

The next meeting of the Japan Micropatterning Committee is scheduled for Tuesday, April 9, 2013 15:30-17:30, at SEMI Japan, Tokyo, Japan.



Respectfully submitted by:
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Minutes approved by:

Iwao Higasikawa (Toshiba), Co-chair	January 21, 2013
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Table 8 Index of Available Attachments #1

#	<i>Title</i>	#	<i>Title</i>
1	JA_Micropatterning_Previous_Mtg_Minutes_121211	3	Ballot_Report_for_5483_121211
2	SEMI_Staff_Report_121211	4	SNARF_of_SEMI-P23_121211

#1 Due to file size and delivery issues, attachments must be downloaded separately. A .zip file containing all attachments for these minutes is available at www.semi.org. For additional information or to obtain individual attachments, please contact Naoko Tejima at the contact information above.